

# NNT 2022 (October 5-7, Toyama Internatinal Conference Center, Toyama, Japan) Program

## October 5, 2022

No.	Time	Paper Title	Author and Affiliation	Country
<b>Room A (2F)</b>				
<b>5A-1: Opening and Plenary Session I (12:00-14:50) → (12:40-14:50)</b>			Chair: Ryutaro Maeda (Xi'an Jiaotong Univ., China) Chair: Helmut Schiff (Paul Scherrer Institute (PSI), Switzerland)	
5A-1-1	12:00-12:10	Opening Remark	Yoshihiko Hirai, Organizing Chair, Osaka Metropolitan Univ., Japan	
5A-1-2	12:10-12:50	Intelligent Nanostructures for Instant Mobile Health Self-Test (Plenary) <del>Withdrawn</del>	Stephen Y. Chou, Essenlix and Princeton Univ., USA	USA
5A-1-3	12:50-13:30	Nanoimprinting – From Niche to High Volume Manufacturing (Plenary)	Thanner Christine, EV Group, Austria	Austria
5A-1-4	13:30-14:10	Nanoimprint Lithography for Semiconductor Manufacturing (Plenary)	Anupam MITRA, KIOXIA, Japan	Japan
5A-1-5	14:10- 14:50	Development of Smart Logistic Solution Using Flexible Sensor with R2R Submicron Electrode Formation Technology (Plenary)	Masayuki Abe, Asahi Kasei, Japan	Japan
<b>5A-2: Video &amp; industry I (14:50-15:40) (Video)</b>				
5A-2-T1	14:50-14:55	GEOMATEC Co., Ltd.		
5A-2-T2	14:55-15:00	Autex Inc.		
5A-2-T3		Meisho Kiko Co., Ltd.		
5A-2-T4	15:00-15:05	Canon Inc.		
5A-2-T5	15:05-15:10	Iwasaki Electric Co., Ltd.		
5A-2-T6	15:10-15:15	Ohara Quartz.Co.,Ltd.		
5A-2-T7	15:15-15:20	TOKYO OHKA KOGYO CO., LTD.		
5A-2-T8	15:20-15:25	ZEON CORPORATION		
5A-2-T9	15:25-15:30	Obuducat Technologies AB		
5A-2-T10	15:30-15:35	Gunei Chemical Industry Co., Ltd.		
5A-2-T11	15:35-15:40	TAZMO CO., LTD.		
5A-2-T12		KYODO INTERNATIONAL INC.		
<b>5A-3: Evening Session I (16:00-17:30)</b>			Chair: Hiroshi Hiroshima (AIST, Japan) Chair: Marc Verschuuren (SCIL Nanoimprint Solutions, The Netherlands)	
5A-3-1	16:00-16:30	Roll-to-Plate Nanoimprint Lithography for mass manufacturing of NanoOptics (Invited)	Jan Matthijs ter Meulen, Erhan Ercan, Kidong Lee and Bram J. F. Titulaer, Morphotonics, The Netherlands	Netherlands
5A-3-2	16:30-16:50	High-resolution nanoimprint lithography of pharmaceutical ingredients containing volatile solvents achieved with gas-permeable porous mold	Rio Yamagishi 1, Sayaka Miura 1, Kaori Yasuda 1, Riku Miyazaki 1, Yuki Kawano 2, Yoshiyuki Yokoyama 2, Naoto Sugino 3, Takao Kameda 3, Satoshi Takei 1, 1 Toyama Pref. Univ., 2 Toyama Industrial Technol. Res. and Development Center and 3 Sanko Gosei, Japan	Japan
5A-3-3	16:50-17:10	Nanoimprinted speckle patterns for mechanical testing using digital image correlation analysis	E.C. Kursun 1, S. Supreeti 2, K.G.F. Janssens 1, H. Schiff 1, P. Spätig 1, 1 Paul Scherrer Inst., Switzerland, 2 Technische Univ. Ilmenau, Germany	Switzerland
5A-3-4	17:10-17:30	Defect reduction technology in replica template process	Ryo Kobayashi, Akihiko Ando, Hideaki Sakurai and Shingo Kanamitsu, Kioxia, Japan	Japan
	17:30-17:50	Break		
<b>5A-4: Evening Session II (17:50-19:20)</b>			Chair: Jun Taniguchi (Tokyo Univ. of Sci., Japan) Chair: Juha Rantala (Inkron Oy, Finland)	
5A-4-1	17:50-18:20	Nanoimprinted meta-surface(meta-lens) (Invited) (Online)	Heon Lee, Korea Univ., Korea	Korea
5A-4-2	18:20-18:40	Chiral Crystallization Directed by Chiral Near-Field Force with Nanostructured Plasmonic Metasurfaces	Hiromasa Niinomi 1, An-Chieh Cheng 2, Teruki Sugiyama 3, Miho Tagawa 4, Hiroshi Yoshikawa 5, Satoshi Uda 1, Tomoya Oshikiri 1 and Masaru Nakagawa 1, 1 Tohoku Univ., 2 Hokkaido Univ., 3 National Yang Ming Chiao Tung Univ., Taiwan, 4 Nagoya Univ., 5 Osaka Univ., Japan	Japan
5A-4-3	18:40-19:00	NIL-Based Patterning of Chemically Strengthened Glasses	João Gaspar 1, Ye Zhou 1, Prasanna Venkatesh Krishnan 1, Kristian Thulin 1, Patrik Lundström 1, Virginia Soares 2 and Virginia Chu 2, 1 Obducat Technologies, Sweden and 2 INESC MN, Portugal	Sweden
5A-4-4	19:00-19:20	Effects of planetary spin-coating on the preparation of thin films for imprinting (Online)	Kazuki Tokumaru and Koichiro Ogata, Natl. Inst. of Technol., Oita College, Japan	Japan

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## October 6, 2022

### Room A (2F)

6A-5: Morning Session I (8:40-10:50)			Chair: Jun Taniguchi (Tokyo Univ. of Sci., Japan) Chair: Joao Gaspar (Obducat Technologies)	
6A-5-1	8:40-9:10	From Visible Wavelengths to Near Infrared: Direct Nanoimprint Lithography for High Aspect Ratio, All-Inorganic Metalenses, Waveguides and Diffractive Optics (Invited)	Vincent J. Einck, Andrew McClung, Dae Eon Jung, Amir Arbabi and <u>James J. Watkins</u> , Univ. of Massachusetts, USA	USA
6A-5-2	9:10-9:30	Filler-Free NIL Compatible Ultra-High Refractive Index Resins for Patterning Diffractive Optical Elements	Carlos Pina-Hernandez and Keiko Munechika, HighRI Optics, USA	USA
6A-5-3	9:30-9:50	Atom-scale-precision fluorescence alignment demonstrated by computational simulation	Hiromasa Niinomi, Subaru Harada, Toshiaki Hayakawa and Masaru Nakagawa, Tohoku Univ., Japan	Japan
6A-5-4	9:50-10:10	High efficiency crystalline metalens with TiO <sub>2</sub> sol gel process	Wonjoong Kim 1, Joohoon Kim 2, Chanwoong Park 1, Hojung Choi 1, Ick Chan Joo 3, Junsuk Rho 2,4,5 and Heon Lee 1, 1 Korea Univ., 2 POSTECH, 3 MIRTEC, 4 POSCO-POSTECH-RIST and 5 NINT, Korea	Korea
6A-5-5	10:10-10:30	Photoluminescence enhancement by electric and magnetic surface lattice resonance in ZrO <sub>2</sub> nanoparticle arrays	M. Higashino, S. Murai, T. Y. Lo, S. Tomita and K. Tanaka, Kyoto Univ., Japan	Japan
6A-5-6	10:30-10:50	Material × Process – critical factors of NIL manufactured optical components	Juha Rantala, Inkron Oy, Finland	Finland

### Foyer (3F)

	10:50-11:10	Coffee Break
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### Room A (2F)

6A-6: Oral & industry I (11:10-11:50)			Chair: Kenichi Nomura (AIST, Japan)	
6A-6-T1	11:10-11:20	GEOMATEC Co., Ltd.		
6A-6-T2	11:20-11:30	Autex Inc.		
6A-6-T3		Meisho Kiko Co., Ltd.		
6A-6-T4	11:30-11:35	Canon Inc. (Video)		
6A-6-T5	11:35-11:40	Iwasaki Electric Co., Ltd. (Video)		
6A-6-T6	11:40-11:50	Ohara Quartz.Co.,Ltd.		
6A-7: Poster Short Presentation (Video) (12:00-14:20)				
6A-7-P1	12:00-12:05	SCIL Nanoimprint Solutions, turning your surfaces into functions; direct patterning of nano-photonics	Marc A. Verschuuren and Jeroen Visser, SCIL Nanoimprint Solutions, The Netherlands	The Netherlands
6A-7-P2	12:05-12:10	Gas-permeable porous mold in nanoimprint lithography for super engineering plastic	Satoshi Takei 1, Sayaka Miura 1, Rio Yamagishi 1, Naoto Sugino 2, Takao Kameda 2, Yuki Kawano 3 and Yoshiyuki Yokoyama 3, 1 Toyama Pref. Univ., 2 Sanko Gosei and 3 Toyama Industrial Technol. Res. and Devel. Center, Japan	Japan
6A-7-P3	12:10-12:15	Formation of the atomically stepped surface of the spin-coated PEDOT:PSS conducting polymer thin film by thermal nanoimprinting	Yuto Maeda 1, Naho Kaneko 1, Tomoaki Oga 1, Satoru Kaneko 2,1, Akifumi Matsuda 1 and Mamoru Yoshimoto 1, 1 Tokyo Inst. of Technol. and 2 Kanagawa Inst. Industrial. Sci. & Technol., Japan	Japan
6A-7-P4	12:15-12:20	Influence of atomic-scale thermal-nanoimprint patterning and surface modification of the polymer substrate on growth of functional oxide thin films	Tomoaki Oga 1, Hisashi Miyazaki 2, Satoru Kaneko 3,1, Akifumi Matsuda 1 and Mamoru Yoshimoto 1, 1 Tokyo Inst. of Technol., 2 Natl. Defense Academy and 3 Kanagawa Inst. of Industrial Sci. and Technol., Japan	Japan
6A-7-P5	12:20-12:25	High Aspect Ratio Nanopillars fabricated by UV Nanoimprint Lithography	Oliver S. Maier 1, Michael J. Haslinger 1, Michael Mühlberger 1, Sonja Kopp 1, Markus Pribyl 2, Philipp Taus 2, Heinz D. Wanzelboeck 2 and Elena Guillen 1, 1 PROFACTOR and 2 Vienna Univ. of Technol., Austria	Austria
6A-7-P6	12:25-12:30	The Study of Bile Duct Stent Having Antifouling Properties Using Biomimetics Technique	Atsushi Sekiguchi 1,2, 1 Osaka Metropolitan Univ. and 2 Litho Tech Japan, Japan	Japan
6A-7-P7	12:30-12:35	Computational study on the releasing process of slanted diffraction structure for AR glasses	1 Ryuhei Yamamura, 2 Yuusei Kunitou, 1 Kai Kameyama, 2 Masaaki Yasuda and 2 Yoshihiko Hirai, 1 Osaka Pref. Univ. and 2 Osaka Metropolitan Univ., Japan	Japan
6A-7-P8	12:35-12:40	Stochastic Simulation of Deactivation Effects in UV Curable Resin	D. Nakamura, Y. Hirai, and M. Yasuda, Osaka Metropolitan Univ., Japan	Japan
6A-7-P9	12:40-12:45	Compatibility of Thermal Property among in Nanoimprint Resin	Kai Kameyama 1, Yuusei Kunitou 2, Hiroaki Kawata 2, Masaaki Yasuda 2 and Yoshihiko Hirai 2, 1 Osaka Pref. Univ. and 2 Osaka Metropolitan Univ., Japan	Japan
6A-7-P10	12:45-12:50	Study on smart process window design for thermal nanoimprint lithography using deep learning systems	Yuusei Kunitou 1, Ryuhei Yamamura 2, Kai Kameyama 2, Masaaki Yasuda 1 and Yoshihiko Hirai 1, 1 Osaka Metropolitan Univ. and 2 Osaka Pref. Univ., Japan	Japan
6A-7-P11	12:50-12:55	Investigation of filling behavior of UV nanoimprint by bridge structure	Yusuke Murakami and Jun Taniguchi, Tokyo Univ. of Sci., Japan	Japan
6A-7-P12	12:55-13:00	Two-tone pattern transfer using nanoimprint and silver ink	K. Enomoto and J. Taniguchi, Tokyo Univ. of Sci., Japan	Japan
6A-7-P13	13:00-13:05	Transfer durability of low concentration release agent coated replica mold with line and space patterns on ultraviolet nanoimprint lithography	Tomohito Wakasa and Jun Taniguchi, Tokyo Univ. of Sci., Japan	Japan

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October 6, 2022				
<b>6A-7-P14</b>	13:05-13:10	Crystal growth of GaN based nanowires using SiO <sub>2</sub> masks formed by nanoimprint lithography process	Mizuki Takahashi, Shiori Yamamura, Yukimi Jinno, Nanami Nakayama, Sae Katsuro, Yuki Yamanaka, Shiori Ii, Ayaka Shima, Soma Inaba, Tetsuya Takeuchi, Motoaki Iwaya, Satoshi Kamiyama, Meijo Univ., Japan	Japan
<b>6A-7-P15</b>	13:10-13:15	Antibacterial property dependent with the nanopillar pitch on the plastic film	Natsuki Ogawa, Tomohiro Shimizu, Shoso Shingubara, Takeshi Ito, Kansai Univ., Japan	Japan
<b>6A-7-P16</b>	13:15-13:20	Effect of nanopillar size on bactericidal and antibacterial properties	Ikki Shingeya, Tomohiro Shimizu, Shoso Shingubara and Takeshi Ito, Kansai Univ., Japan	Japan
<b>6A-7-P17</b>	13:20-13:25	Selection of adhesive molecular layers with monomer-repellence and chemisorption for a shape-fixed residual layer in UV nanoimprint lithography	Kanta Kawasaki, Akiko Onuma, Hiromasa Niinomi, and Masaru Nakagawa, Tohoku Univ., Japan	Japan
<b>6A-7-P18</b>	13:25-13:30	Prediction of Durability of the Mold for Production of Nanostructures in Ultraviolet Nanoimprint Lithography (UV-NIL) using Machine Learning	Yuta Aoki, Junichiro Ono, Tomohito Wakasa, Jun Taniguchi and Shin-ichi Satake, Tokyo Univ. of Sci., Japan	Japan
<b>6A-7-P19</b>	13:30-13:35	Molecular dynamics study of effects of loading pressure on shear properties of organic nanofilms	Naoki Matamoto and Kazuhiro Tada, National Inst. of Technol., Toyama College, Japan	Japan
<b>6A-7-P20</b>	13:35-13:40	Fabrication of Ag nanoantenna sticker and application to luminescence control	TienYang Lo, Shunsuke Murai and Katsuhisa Tanaka, Kyoto Univ., Japan	Japan
<b>6A-7-P21</b>	13:40-13:45	Fabrication of Flexible Sticker of Si metasurface by a Transfer Process	Yuto Inoue, Shunsuke Murai and Katsuhisa Tanaka, Kyoto Univ., Japan	Japan
<b>6A-7-P22</b>	13:45-13:50	Fabrication of rose petal effect film by moth-eye structure mold and photolithography	Kazuki Arai, Takuto Wakasa, Kazuki Fujiwara and Jun Taniguchi, Tokyo Univ. of Sci., Japan	Japan
<b>6A-7-P23</b>	13:50-13:55	Analysis of resistance against deformation stress of nanofilaments inside clingfish mimicked tape by using FEM simulation	Kazuma Tsujioka 1, Yasutaka Matsuo 1,3, Yuji Hirai 2 and Masatsugu Shimomura 2, 1 Hokkaido Univ. and 2 CIST, Japan	Japan
<b>6A-7-P24</b>	13:55-14:00	Nanoimprint and nanoprint processes using Seamless Roller Mold	Makoto Okada, Asahi Kasei, Japan	Japan
<b>6A-7-P25</b>	14:00-14:05	Micromolds for glass molding by the carbonization of epoxy resist made by laser direct write lithography ( <a href="#">Online</a> )	Muhammad Refatul Haq and Helmut Schiff, Paul Scherrer Inst., Switzerland	Switzerland
<b>6A-7-P26</b>	14:05-14:10	Fabrication of self-standing PMMA film with 0.5 μm through-holes by imprint and photolithography hybrid process	H. Kawata, M. Yasuda, Y. Hirai, and H. Kikuta, Osaka Metropolitan Univ., Japan	Japan
<b>6A-7-P27</b>	14:10-14:15	Imprint process for glass nano-patterning using silica nano powder	Yu Kubota and Fujio Tsumori, Kyushu Univ., Japan	Japan
<b>6A-7-P28</b>	14:15-14:20	MICRO-POWDER-IMPRINTING USING MOLDS WITH SIMILAR SCALE TO CERAMIC NANO PARTICLE	Ryoma Taira and Fujio Tsumori, Kyushu Univ., Japan	Japan
<b>Foyer (3F)</b>				
<b>6A-8: Poster session &amp; Industrial exhibition On-site (14:20-16:00)</b>				
<b>6A-8</b>	14:20-16:00	Poster Session		
<b>Room A (2F)</b>				
<b>6A-9: Evening Session III (16:00-17:30)</b>		Chair: Jan Matthijs ter Meulen (Morphotonics, The Netherlands) Chair: Kenichi Nomura (AIST, Japan)		
<b>6A-9-1</b>	16:00-16:30	Electric-field-driven Jet Deposition Micro-nano 3D Printing and its Applications in Manufacturing Advanced Circuits and Electronics ( <a href="#">Invited</a> ) ( <a href="#">Online</a> )	Hongbo Lan, Xiaoyang Zhu and Guangming Zhang, Qingdao Univ. of Technol., China	China
<b>6A-9-2</b>	16:30-16:50	Hierarchical Micro-/Nanostructured Substrates for the Growth of Cardiomyocytes made by Nanoimprint Lithography	Michael Mühlberger 1, Sonja Kopp 1, Alison Deyett 2, Markus Pribyl 3, Michael Haslinger 1, Anica Siegel 1, Philipp Taus 3, Elena Guillen 1, Aranxa Torres Caballero 2, Bozhidar Baltov 4, Leif Yde 5, Jan Stensborg 5, Sasha Mendjan 2, Steffen Hering 4, Heinz D. Wanzenboeck 3, 1 PROFACTOR, Austria, 2 Institute of Molecular Biotechnology, 3 Technical Univ. Wien, 4 Chanpharm, Austria and 5 Stensborg, Denmark	Austria
<b>6A-9-3</b>	16:50-17:10	Development of optical anti-reflection with anti-fogging property combined with nanostructure and specially designed vacuum deposition	Kazuma Kurihara and Hokari Ryohei, AIST, Japan	Japan
<b>6A-9-4</b>	17:10-17:30	Analysis of Elastic Contacts in Chemical Mechanical Polishing by using Nanoimprint Lithography as a Characterization Method	Joscha S. Kappel 1, Robert Kirchner 2, Sascha Bott 3, Benjamin Lilienthal-Uhlig 1, Johann W. Bartha 2, 1 Fraunhofer-IPMS, 2 Dresden Univ. of Technol., 3 GlobalFoundries Dresden Module One, Germany	Germany
<b>Foyer (3F)</b>				
	17:30-17:50	Coffee Break		
<b>Room A (2F)</b>				
<b>6A-10: Evening Session IV (17:50-19:00)</b>		Chair: Koji Asakawa (KIOXIA, Japan) Chair: Kenichi Nomura (AIST, Japan)		
<b>6A-10-1</b>	17:50-18:20	Demonstration of Micromirror Fabrication for Co-packaged Optics Using UV Nanoimprint ( <a href="#">Invited</a> )	F. Nakamura 1, K. Suzuki 2, A. Noriki 2 and T. Amano 2, 1 PETRA and 2 AIST, Japan	Japan
<b>6A-10-2</b>	18:20-18:40	Combining UV-curable polymeric materials for advanced optical designs ( <a href="#">Online</a> )	M. Brehm, R. Richter, M. Trinkwalder, M. Follner and S. Prinz, DELO Industrial Adhesives, Germany	Germany
<b>6A-10-3</b>	18:40-19:00	Antibacterial film using oligoglucosamine derivatives in nanoimprint lithography utilizing biomimetics technology	Sayaka Miura 1, Rio Yamagishi 1, Riku Miyazaki 1, Kaori Yasuda 1, Naoto Sugino 2, Takao Kameda 2, Yuki Kawano 3, Yoshiyuki Yokoyama 3, Satoshi Takei 1, 1 Toyama Prefectural Univ., 2 Sanko Gosei and 3 Toyama Industrial Technol. Res. and Development Center Japan	Japan

# NNT 2022 (October 5-7, Toyama Internatinal Conference Center, Toyama, Japan) Program

## October 7, 2022

### Room A (2F)

<b>7A-11: Morning Session II (9:00-10:50)</b>		Chair: Koji Asakawa (KIOXIA, Japan) Chair: Michael Mühlberger (PROFACTOR, Austria)		
<b>7A-11-1</b>	9:00-9:30	Ultra-High Throughput Electron Beam Lithography System for Nanoimprint Mold Fabrication <span style="color: red;">(Invited)</span>	Takaomi Ito 1, Takumi Watanabe 1, Satoshi Nagai 1, Sung-won Youn 2, Kenta Suzuki 2 and Hiroshi Hiroshima 2, 1 Elionix and 2 AIST, Japan	Japan
<b>7A-11-2</b>	9:30-9:50	Nanofabrication of metal/semiconductor/metal structure for efficient photocathode under strong coupling condition	Tomoya Oshikiri 1, Xu Shi 2, Hiroaki Misawa 2,3 and Masaru Nakagawa 1, 1 Tohoku Univ., 2 Hokkaido Univ., Japan and 3 National Yang Ming Chiao Tung Univ., Taiwan	Japan
<b>7A-11-3</b>	9:50-10:10	Nanoimprint-based plasmonic/non-plasmonic lattices for controlling light	Shunsuke Murai and Katsuhisa Tanaka, Kyoto Univ., Japan	Japan
<b>7A-11-4</b>	10:10-10:30	A novel optical diffuser inspired by Morpho butterfly's nanostructure enables skillful light diffusion and self-cleaning properties	Kazuma Yamashita 1, Takuma Hattori 1,2, Yuji Kuwahara 1,2 and Akira Saito 1,2, 1 Osaka Univ. and 2 RIKEN Spring-8, Japan	Japan
<b>7A-11-5</b>	10:30-10:50	Simple Preparation of the Multi-functional Vulcanized Rubber Microstructures	Yuji Hirai 1, Syun Uemura 1, Yasutaka Matsuo 2, Takahiro Okamatsu 3, Toshihiko Arita 4, Masatsugu Shimomura 1, 1 Chitose Institute of Technol., 2 Hokkaido Univ., 3 YOKOHAMA RUBBER and 4 Tohoku Univ., Japan	Japan
	10:50-11:00	Break		
<b>7A-12: Oral &amp; Industry II (11:00-11:50)</b>		Chair: Jun Taniguchi (Tokyo Univ. of Sci., Japan)		
<b>7A-12-T7</b>	11:00-11:05	TOKYO OHKA KOGYO CO., LTD. <span style="color: blue;">(Video)</span>		
<b>7A-12-T8</b>	11:05-11:15	ZEON CORPORATION		
<b>7A-12-T9</b>	11:15-11:25	Obuducat AB		
<b>7A-12-T10</b>	11:25-11:35	Gunei Chemical Industry Co., Ltd.		
<b>7A-12-T11</b>	11:35-11:40	TAZMO CO., LTD. <span style="color: blue;">(Video)</span>		
<b>7A-12-T12</b>	11:40-11:50	KYODO INTERNATIONAL INC.		
<b>7A-13: Plenary session II (12:10-14:20)</b>		Chair: Yoshihiko Hirai (Osaka Pref. Univ., Japan) Chair: James J. Watkins (Univ. of Massachusetts, USA)		
<b>7A-13-1</b>	12:10-12:50	Development of Nanoimprint Lithography Tool <span style="color: red;">(Plenary)</span>	Toshiki Ito, CANON, Japan	Japan
<b>7A-13-2</b>	12:50-13:30	Nanoimprint Technology for Plasmonic Sensors and Metadevices <span style="color: red;">(Plenary)</span> <span style="color: blue;">(Online)</span>	Stella W. Pang, City University of Hong Kong, Hong Kong, China	Hong Kong
<b>7A-13-3</b>	13:30-14:10	Back to the future - nanoimprint revisited <span style="color: red;">(Plenary)</span>	Helmut Schift, Paul Scherrer Institut, Switzerland	Switzerland
<b>7A-13-4</b>	14:10-14:20	Award Ceremony Closing Remark:	James J. Watkins (Univ. of Massachusetts, USA)	



## 3F Technical Exhibition List

- 1 GEOMATEC Co., Ltd.
- 2 Autex Inc.
- 3 MEISYO KIKO Co., Ltd.
- 4 Canon Inc.
- 5 Iwasaki Electric Co., Ltd.
- 6 TOKYO OHKA KOGYO CO., LTD.
- 7 Ohara Quartz.Co.,Ltd.
- 8 ZEON CORPORATION
- 9 Obducat Technologies AB
- 10 TAZMO CO., LTD.
- 11 Gunei Chemical Industry Co., Ltd.
- 12 KYODO INTERNATIONAL INC.

## 3F Poster Session

**6A-7: Poster Short Presentation (Video)**  
(12:00-14:20, October 6)

**6A-8: Poster session & Industrial exhibition On-site**  
(14:20-16:00, October 6)

Poster Panel Available: 9:00-11:00  
Poster Remove: 16:00-17:50



## 2F Registration Desk

All participants are requested to register at the registration desk. Please give your name to get your name card.

## 2F Session Registration Desk

All authors are requested to register at the session registration desk no later than 30 min. before the session starts. Please pick a name card point (blue) up there.

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